

# Three-dimensional modeling of argon flow in floating zone crystal growth process

Andrejs Sabanskis, Jānis Virbulis

*Faculty of Physics and Mathematics, University of Latvia*

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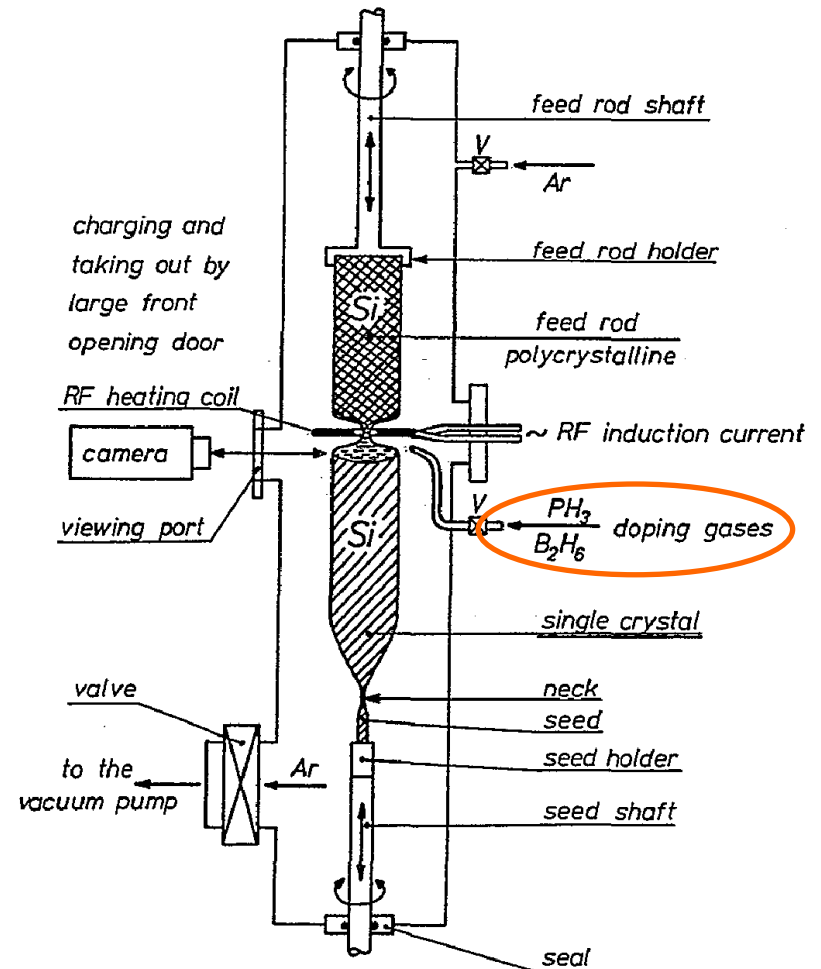


# Introduction

## *Si single crystal growth with FZ technique*



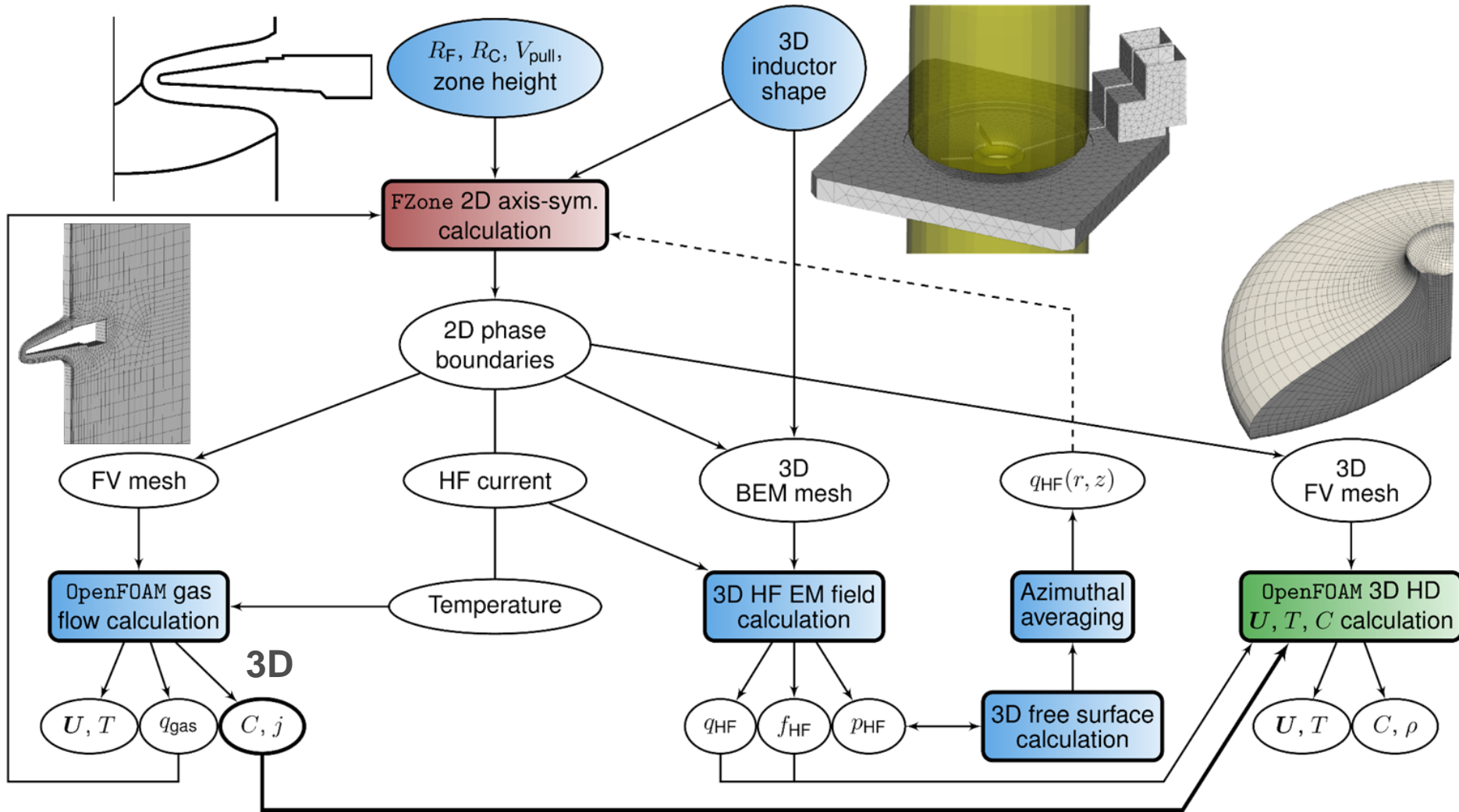
Courtesy of Dr. H. Riemann (ICG, Berlin)



W. Zulehner. Mater. Sci. Eng. B, 73(1):7-15, 2000

# Introduction

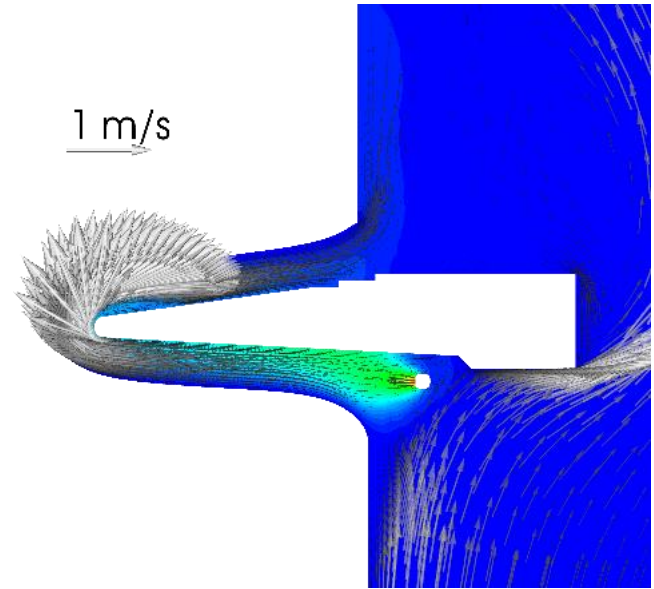
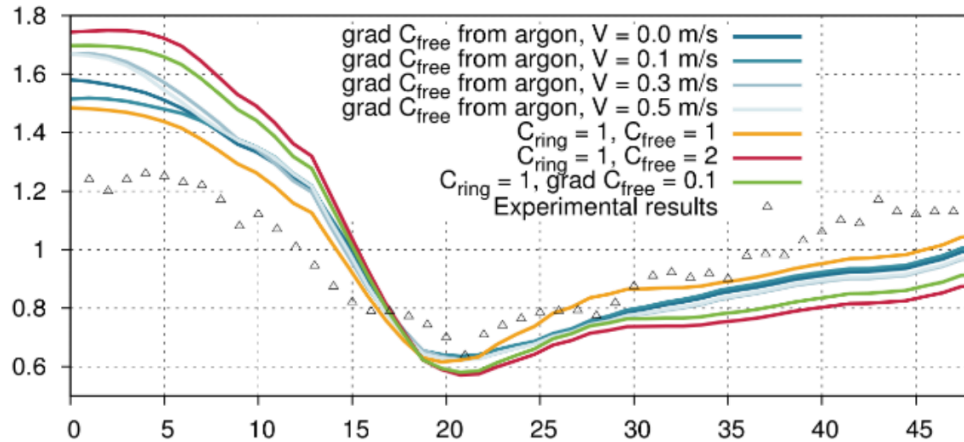
## *Actual mathematical model*



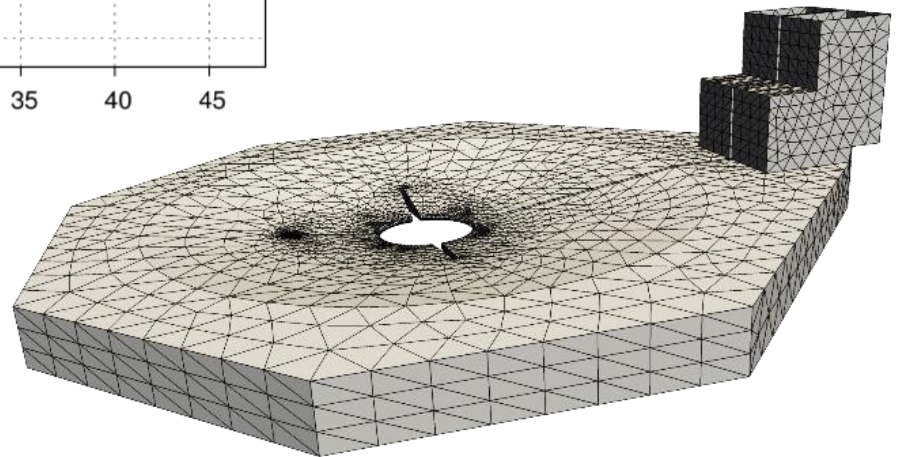
# Introduction

## *Motivation for 3D gas flow calculations*

- Previous axisymmetric calculations: insufficient agreement of radial resistivity variations with experiment



- 3D inductor shape and non-symmetric dopant inlet



# Mathematical models

## *3D gas flow and dopant transport*

Continuity and momentum equations

$$\nabla(\rho \mathbf{U}) = 0$$

$$\nabla \left( \rho \mathbf{U} \otimes \mathbf{U} + \frac{2}{3} \mu_{\text{eff}} \nabla \mathbf{U} - 2 \mu_{\text{eff}} \mathbf{e} \right) = -\nabla p_{\text{rgh}} - \mathbf{g} x \nabla \rho, \quad p_{\text{rgh}} = p - \rho \mathbf{g} x$$

Turbulence:

k-omega SST

Energy equation

$$\rho \mathbf{U} \nabla \left( \tilde{h} + \frac{U^2}{2} \right) = \nabla (\alpha_{\text{eff}} \nabla h)$$

Ideal gas law

$$\rho = p \frac{M_g}{RT}$$

Specific enthalpy  $\tilde{h} = c_p T$

Dopant transport equation

$$(\rho \mathbf{U} \nabla) C = \nabla (\rho D_{\text{eff}} \nabla C), \quad \rho D_{\text{eff}} = \frac{\mu}{Sc} + \frac{\mu}{Sc_t}$$

Viscosity: Sutherland's law

$$\mu(T) = \frac{A_S \sqrt{T}}{1 + T_S/T}$$

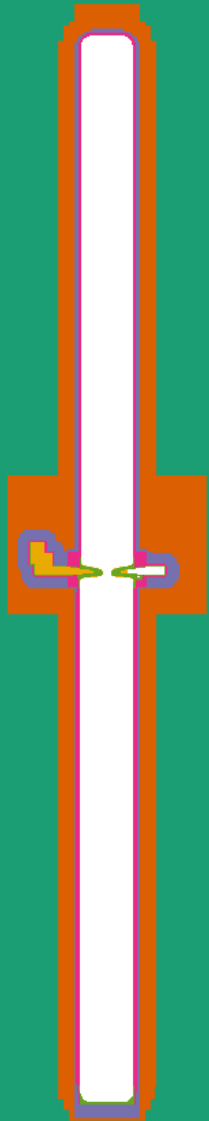
Dopant mass flux

$$\mathbf{j} = -\rho D_{\text{eff}} \frac{\partial C}{\partial n}$$

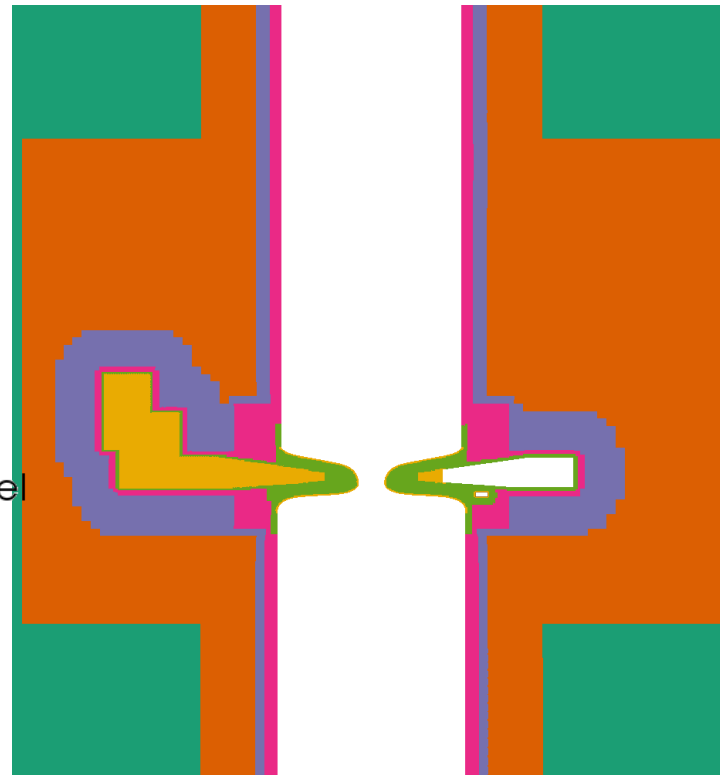


# Creation of 3D mesh

*OpenFOAM utility snappyHexMesh*

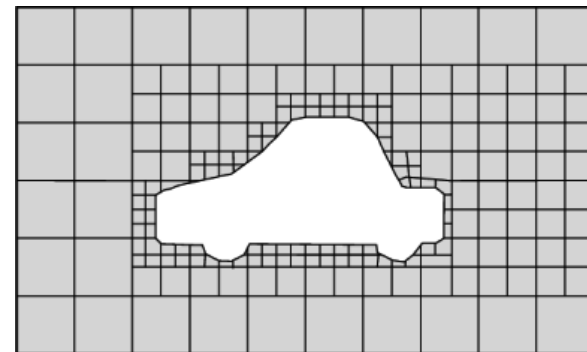
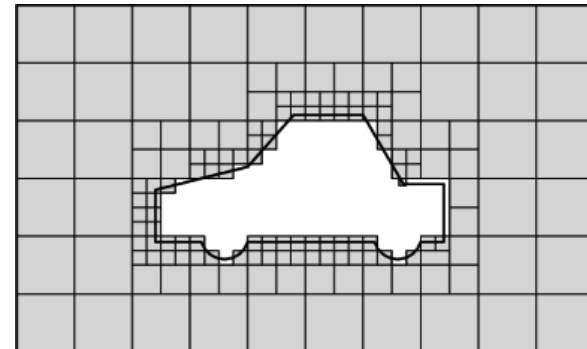
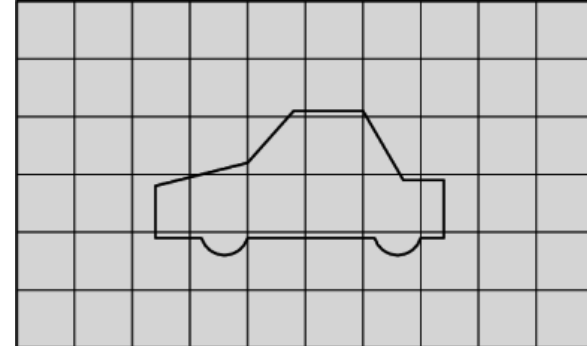


cellLevel



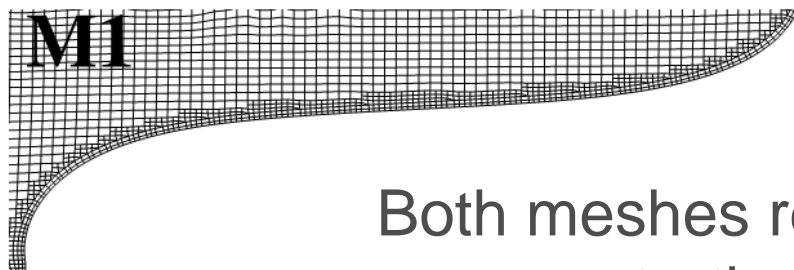
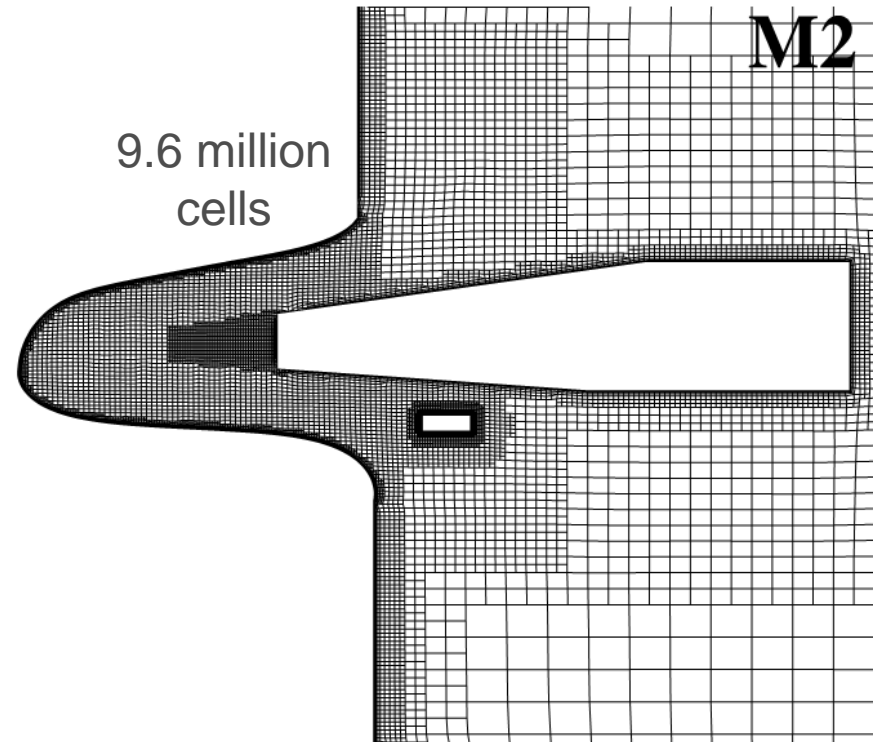
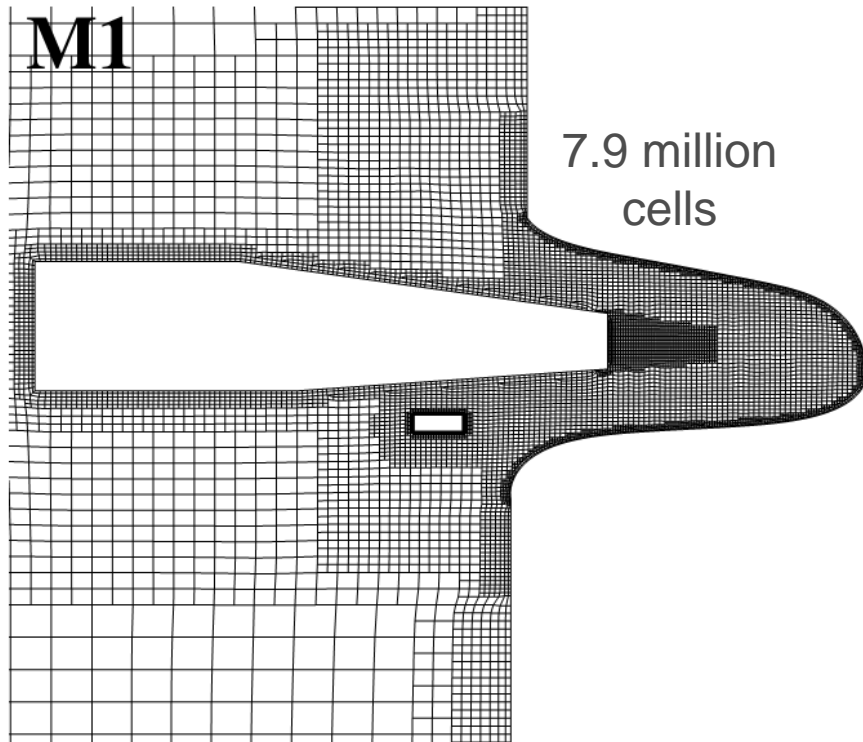
cellLevel is the number of refinements of basic mesh:  
0 – no refinement, 1 – 2x2x2,  
2 – 4x4x4, and so on

<http://www.openfoam.org/docs/user/snappyHexMesh.php>



# Creation of 3D mesh

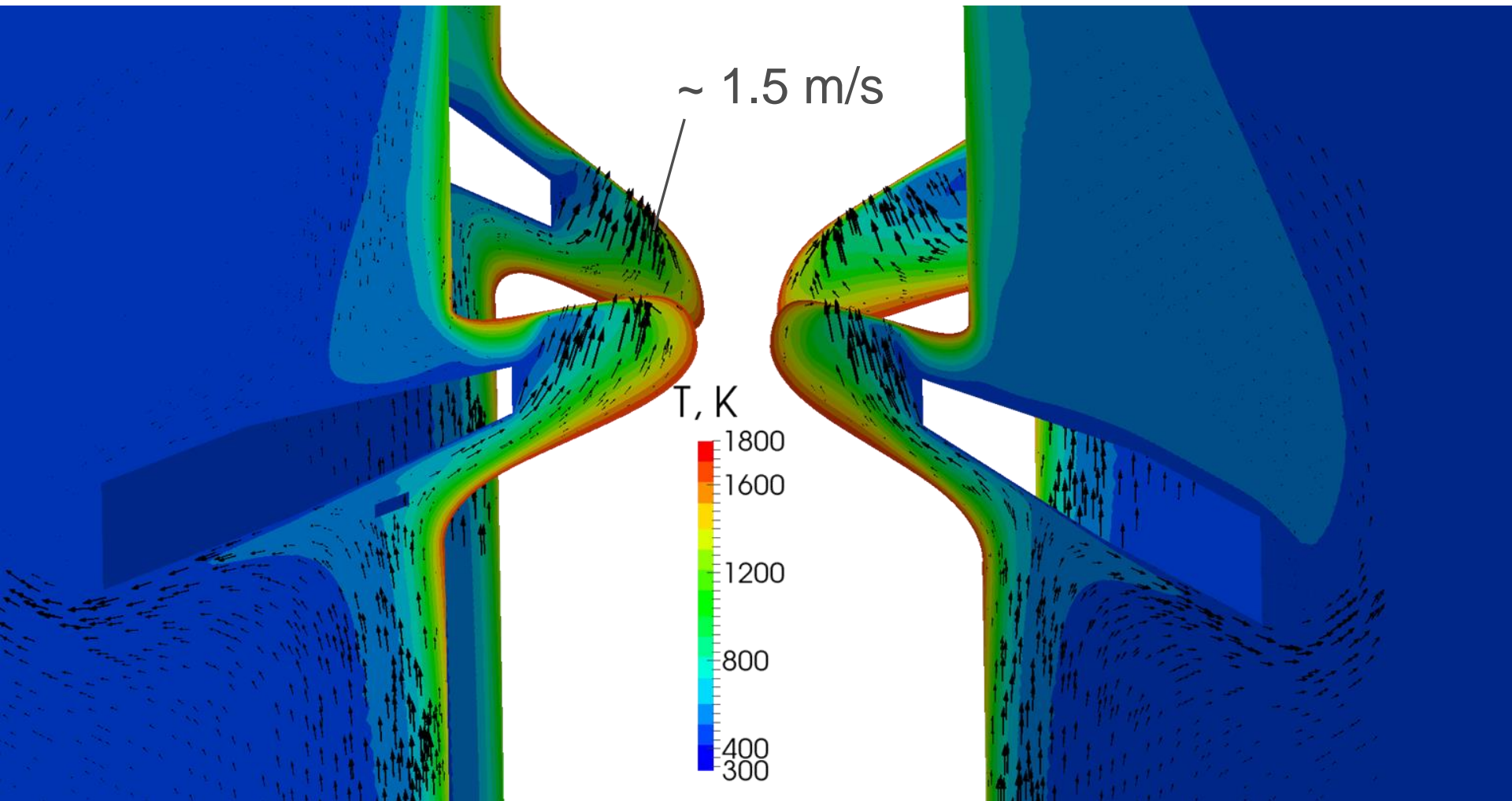
## *Mesh influence study*



Both meshes resolve temperature and concentration boundary layers well

# Calculation results

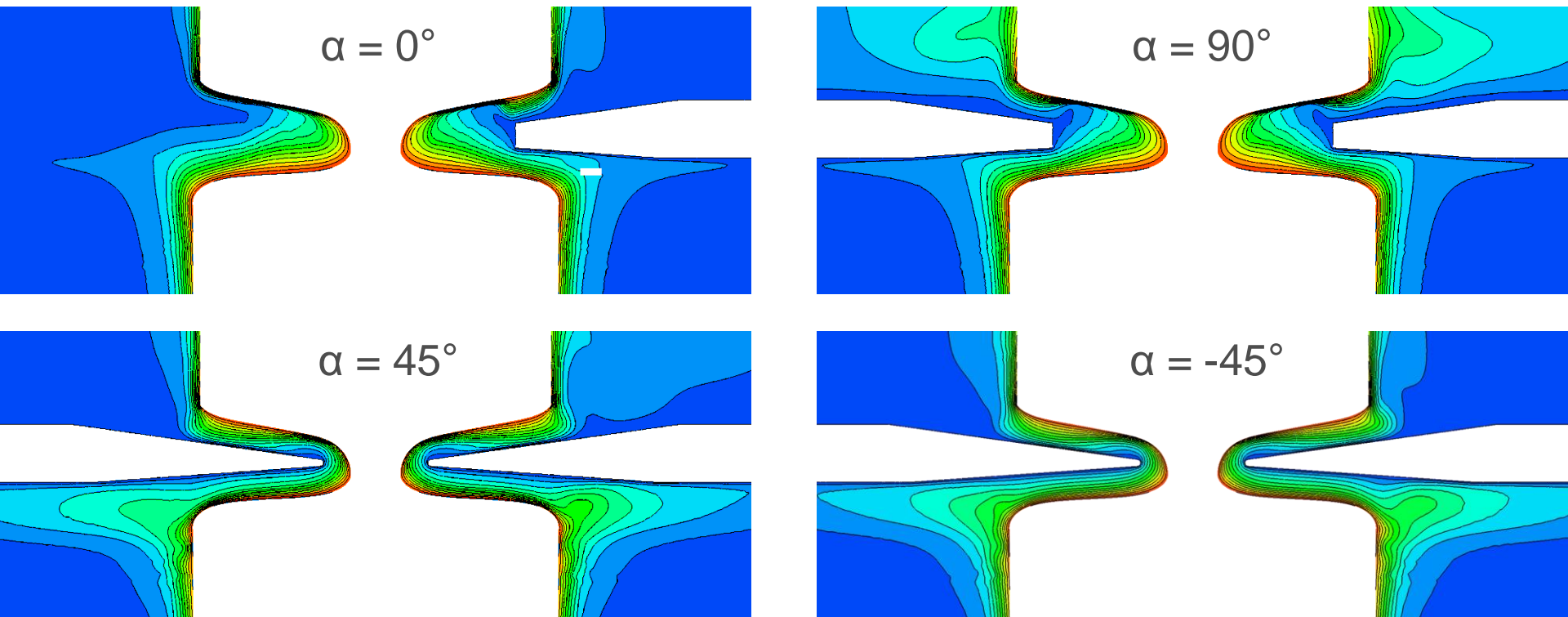
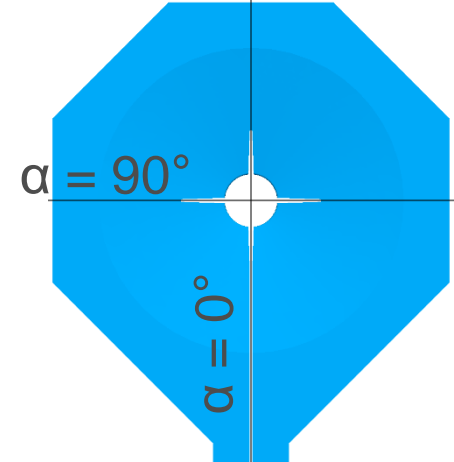
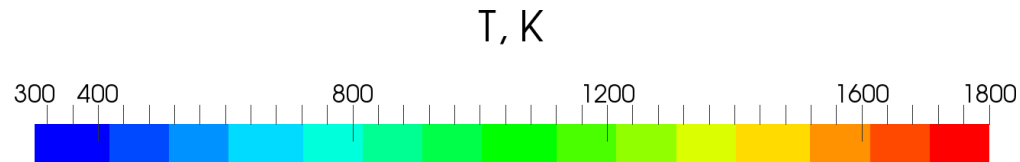
## *Temperature field*





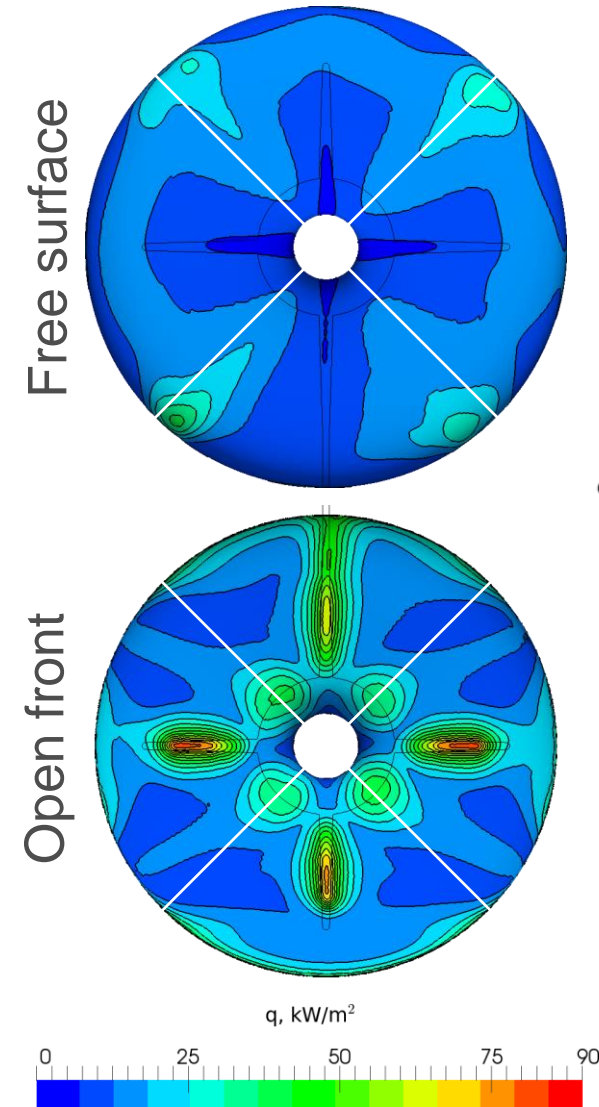
# Calculation results

## *Temperature field*

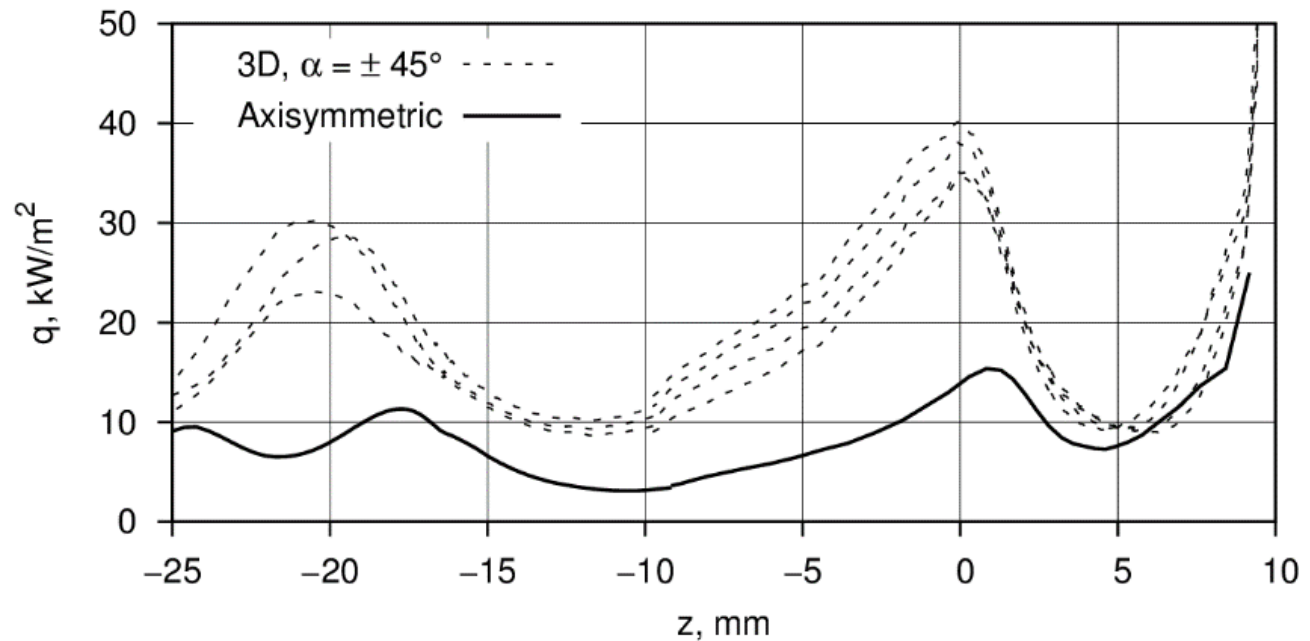


# Calculation results

## *Gas cooling heat flux density*



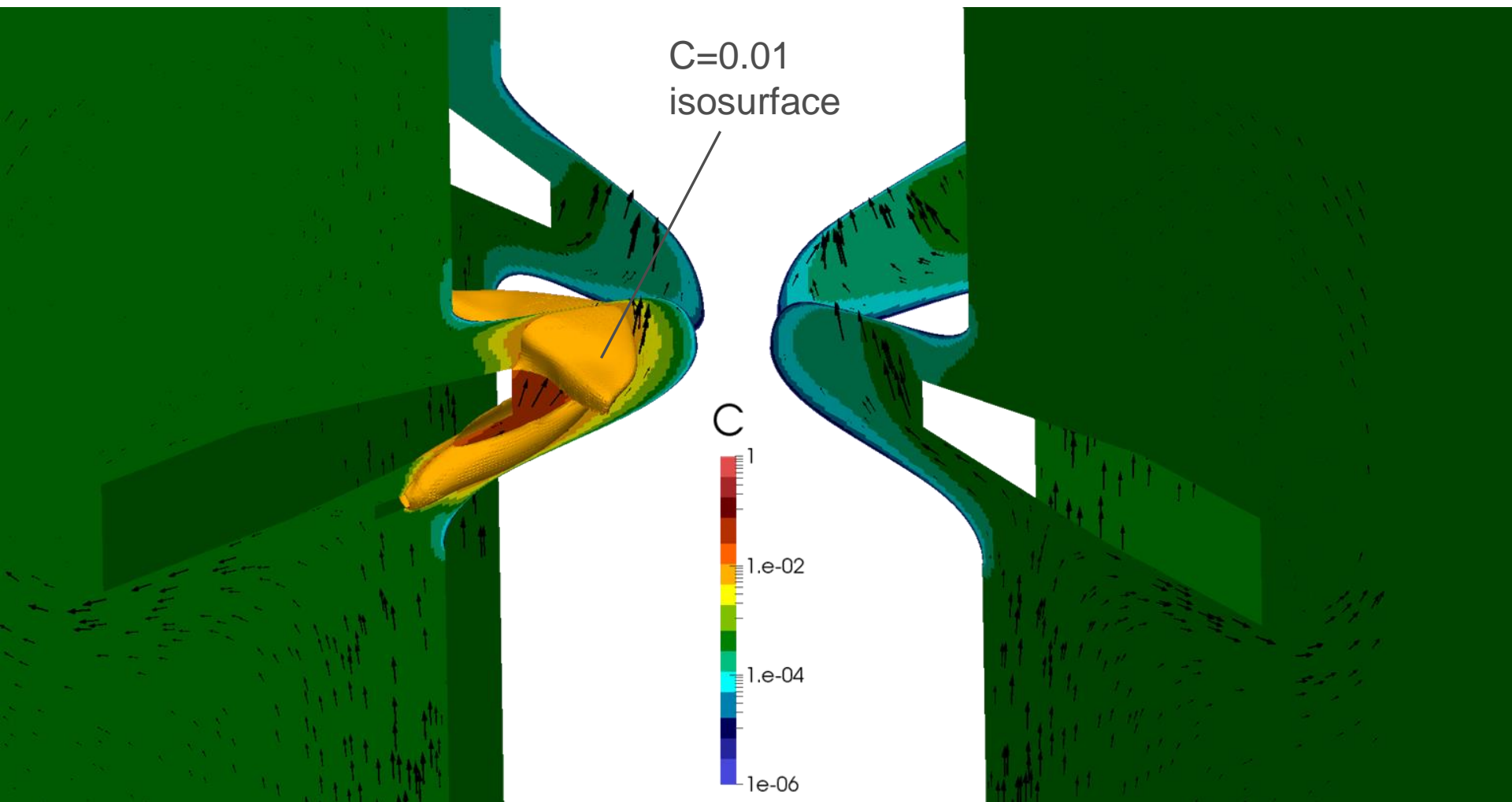
Comparison with previous  
axisymmetric calculations



Free surface ← → Open front

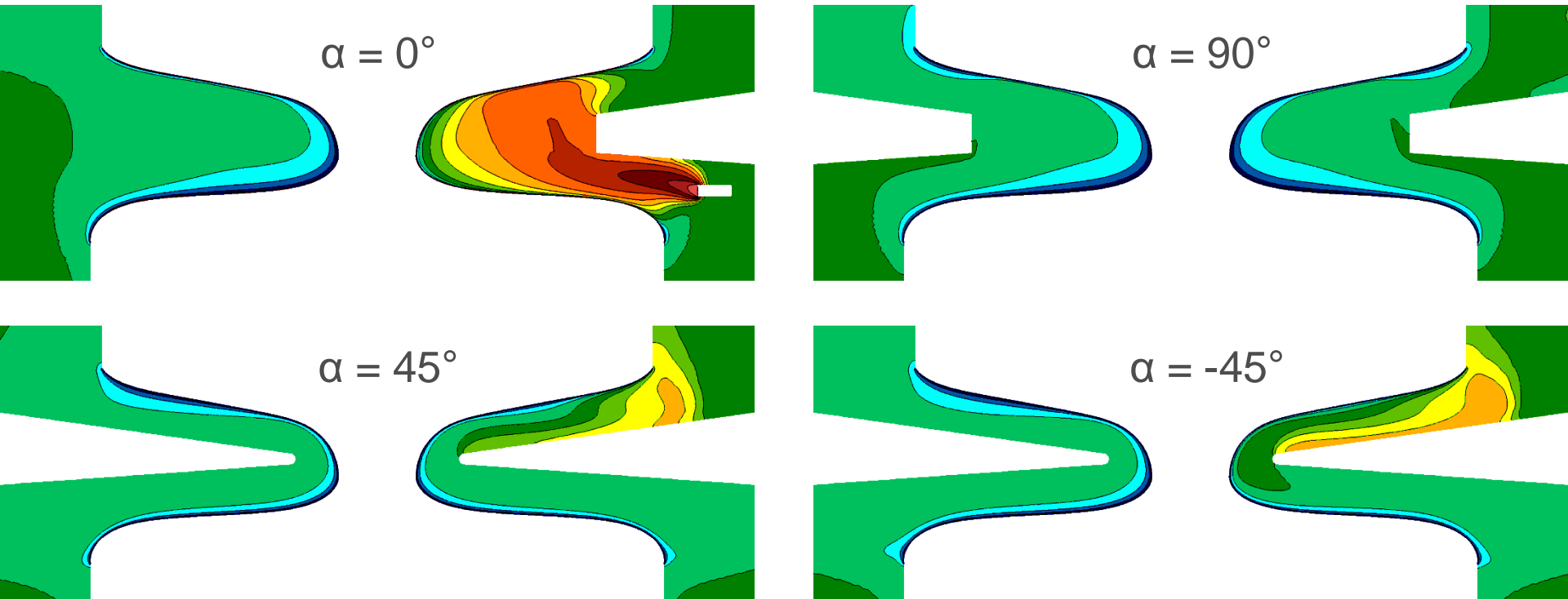
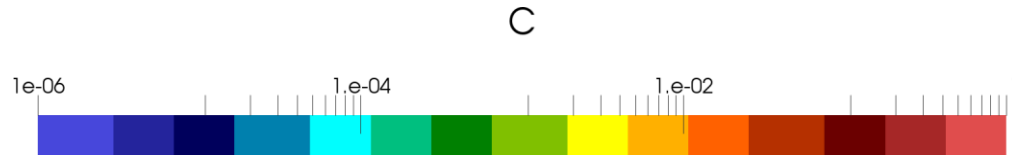
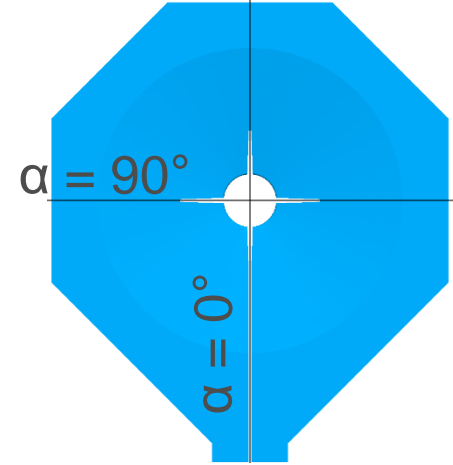
# Calculation results

## *Dopant concentration*



# Calculation results

## *Dopant concentration*





# Conclusions and outlook

1. 3D gas flow calculations in FZ puller have been carried out for the first time
2. snappyHexMesh is hard to master, but it is suitable for mesh generation in a complex geometry
3. Calculated fields are strongly three-dimensional; symmetry is obtained with respect to the plane of main inductor slit
4. 3D calculations predict stronger gas cooling than previous axisymmetric simulations
5. The obtained concentration field and dopant mass fluxes at Si surfaces are used to create non-symmetric boundary conditions for 3D HD simulation of liquid Si flow (these results are not included in the present talk)